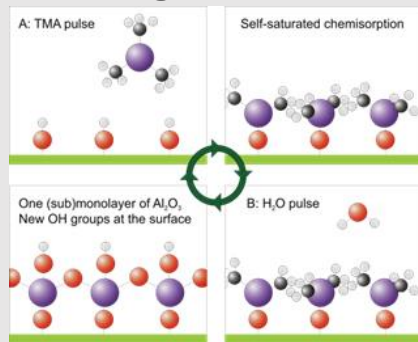


Atomic layer deposition and X-ray characterisation of mirror coatings

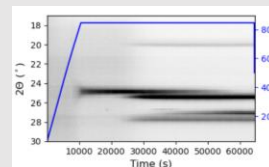
Jorden De Bolle, Jolien Dendooven, Christophe Detavernier

Amorphous coatings

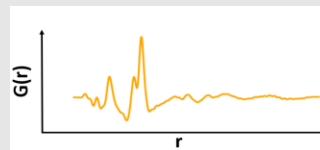
Deposition of amorphous coatings with ALD



X-ray characterisation of mirror coatings



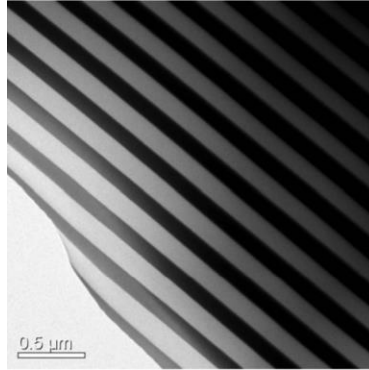
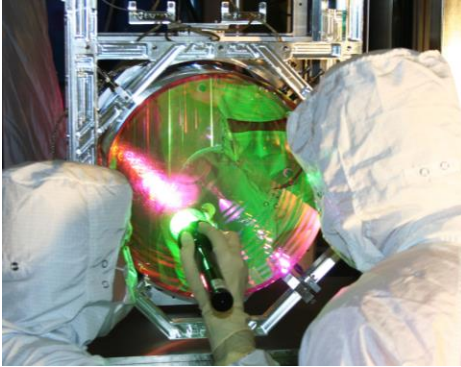
In-situ XRD
(collaboration with
VCR&D)



PDF analysis
(funded by IRI)

Deposition of amorphous coatings with ALD

Why different deposition techniques

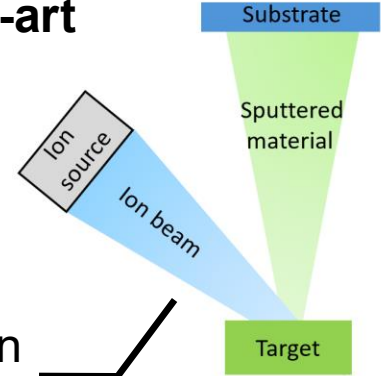


Current state-of-the-art

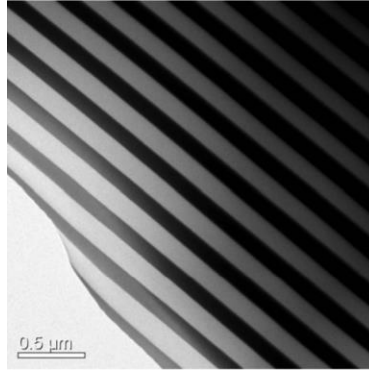
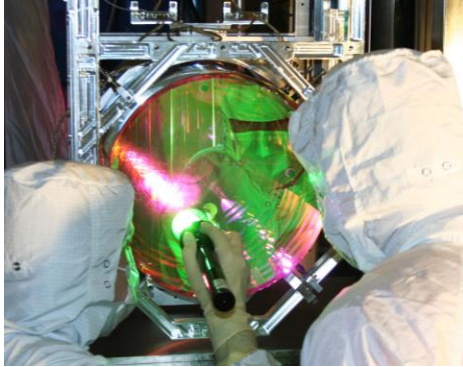
Alternating layers

of amorphous
 $\text{Ti:Ta}_2\text{O}_5$ and SiO_2

Deposited with ion
beam sputtering (IBS)



Why different deposition techniques



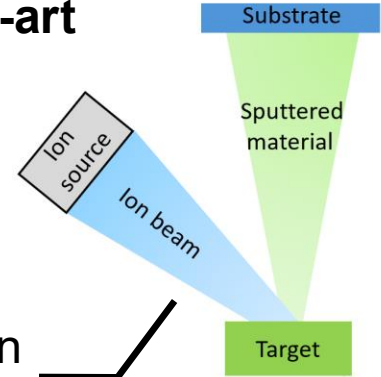
Current state-of-the-art

Alternating layers

of amorphous

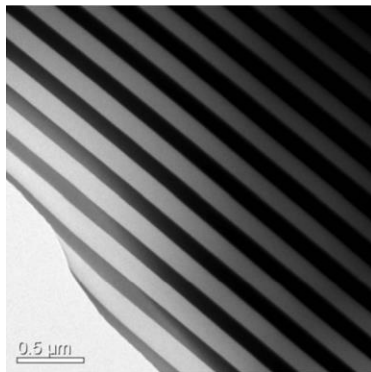
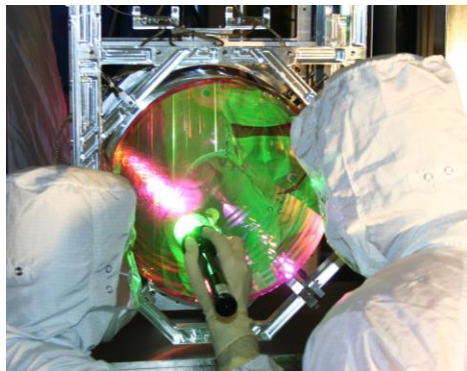
Ti:Ta₂O₅ and SiO₂

Deposited with ion
beam sputtering (IBS)



Optical and mechanical properties of amorphous materials depend on the stability of coating structure, which can change depending on the deposition process

Why different deposition techniques



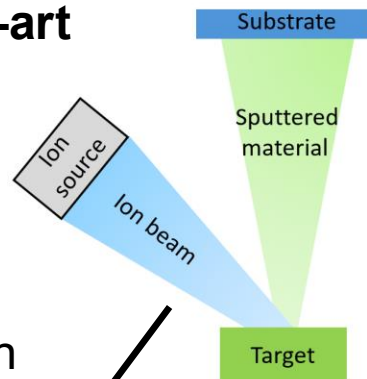
Current state-of-the-art

Alternating layers

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Ti:Ta₂O₅ and SiO₂

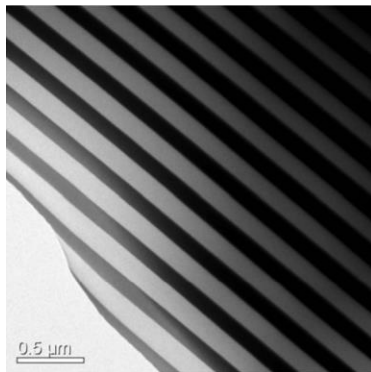
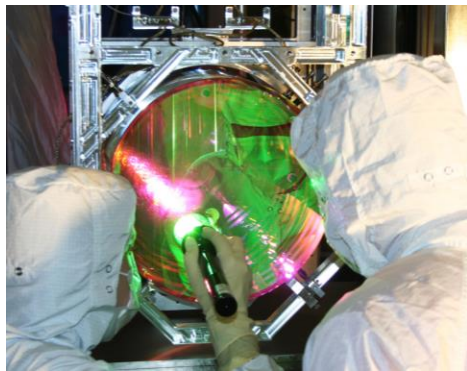
Deposited with ion
beam sputtering (IBS)



Optical and mechanical properties of amorphous materials depend on the stability of coating structure, which can change depending on the deposition process

✓ A different deposition technique might result in coatings with better performance

Why different deposition techniques

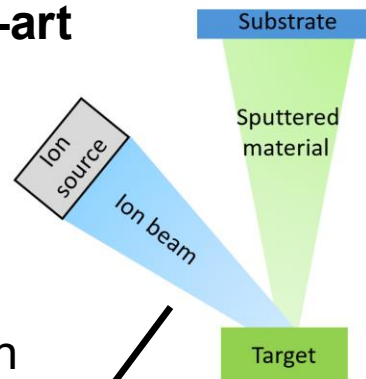


Current state-of-the-art

Alternating layers

of amorphous
 $\text{Ti:Ta}_2\text{O}_5$ and SiO_2

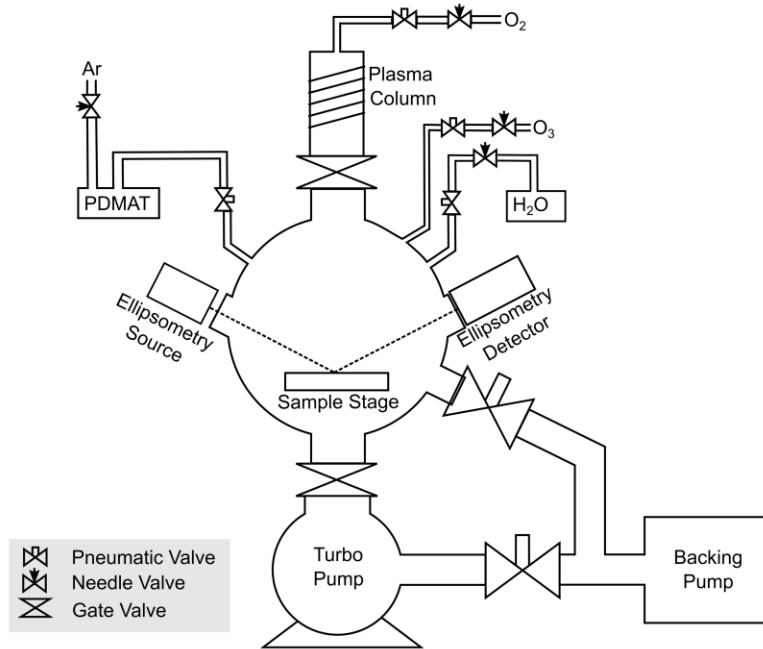
Deposited with ion
beam sputtering (IBS)



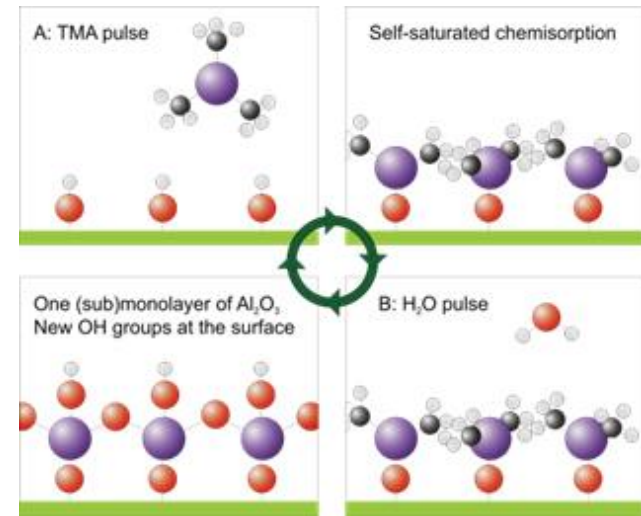
Optical and mechanical properties of amorphous materials depend on the stability of coating structure, which can change depending on the deposition process

- ✓ A different deposition technique might result in coatings with better performance
- ✓ A different deposition technique gives opportunities to get more insight in loss mechanisms

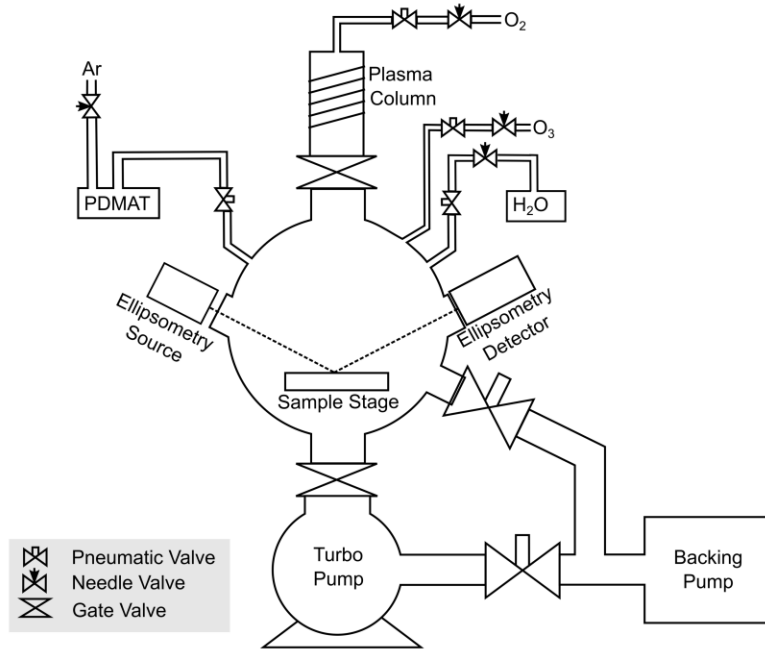
Atomic layer deposition (ALD)



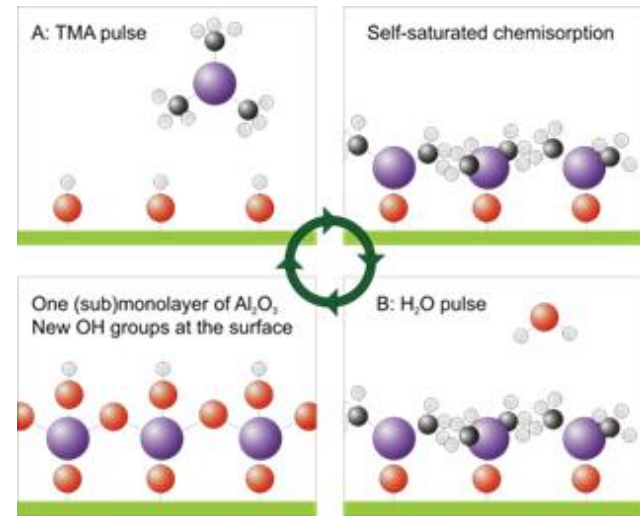
Self-limiting reactions between
substrate and precursor gases!



Atomic layer deposition (ALD)

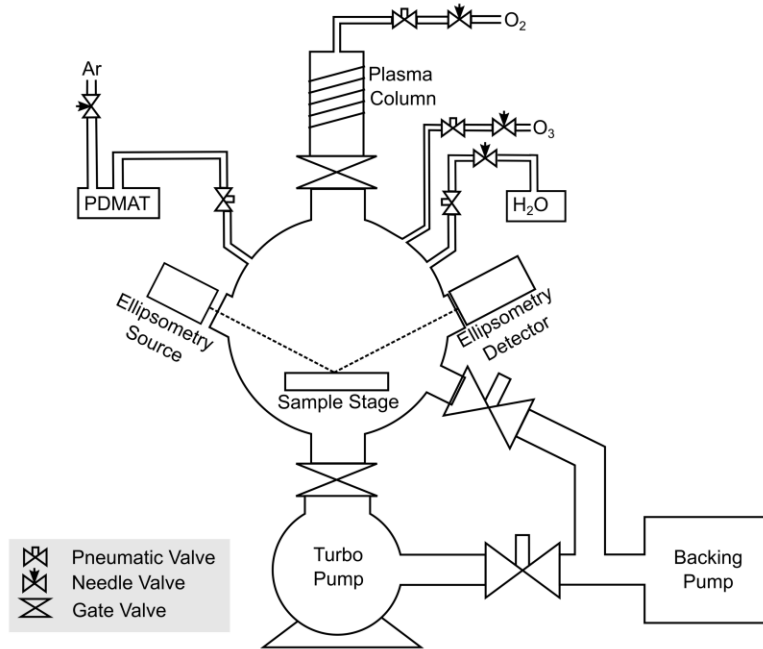


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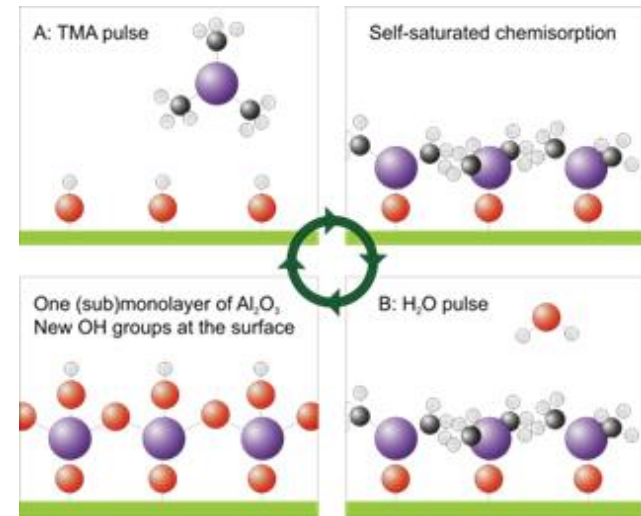


Atomic thickness control

Atomic layer deposition (ALD)

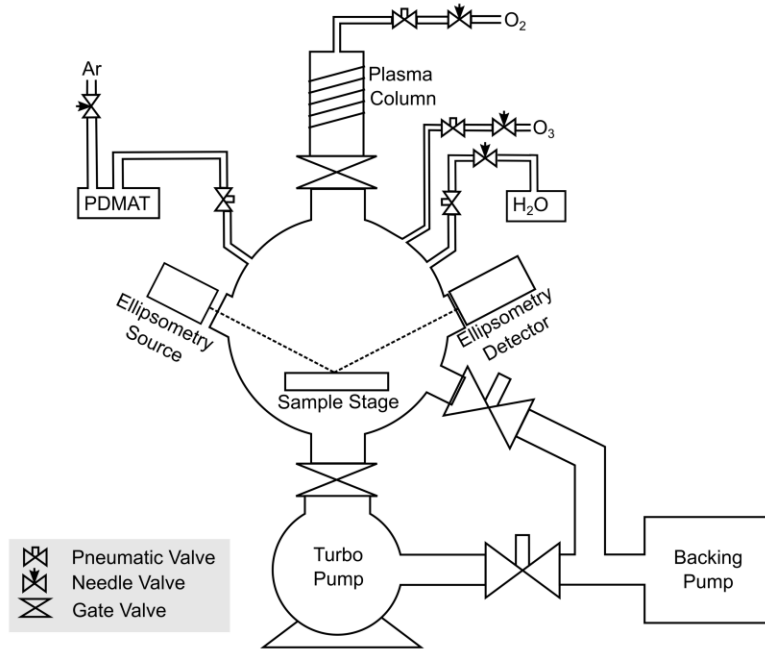


Self-limiting reactions between
substrate and precursor gases!

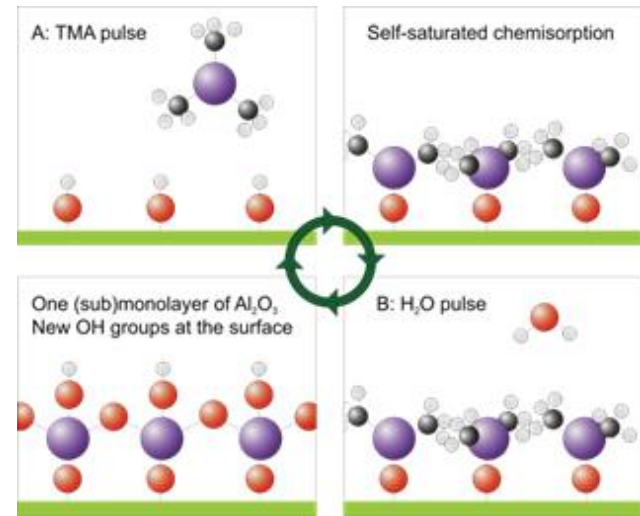


- ✓ Atomic thickness control
- ✓ Superior uniformity

Atomic layer deposition (ALD)

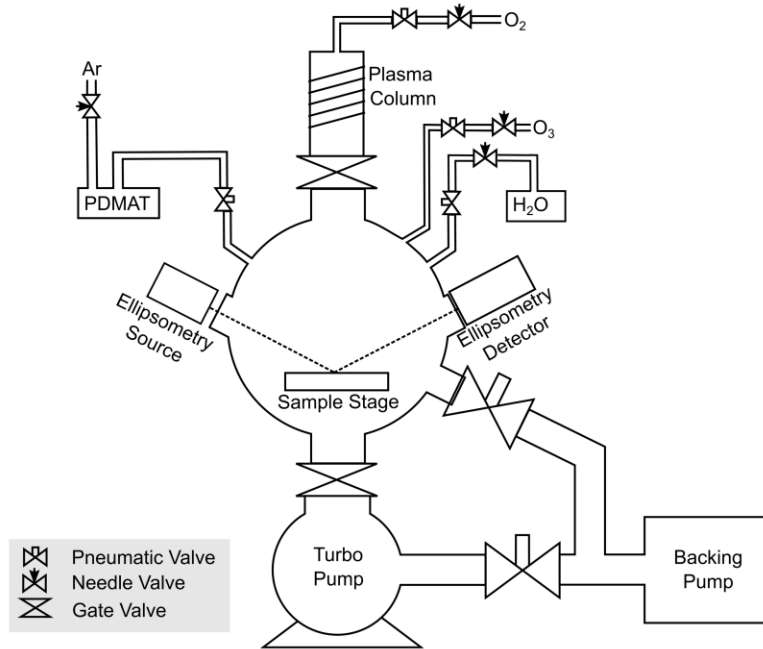


Self-limiting reactions between substrate and precursor gases!

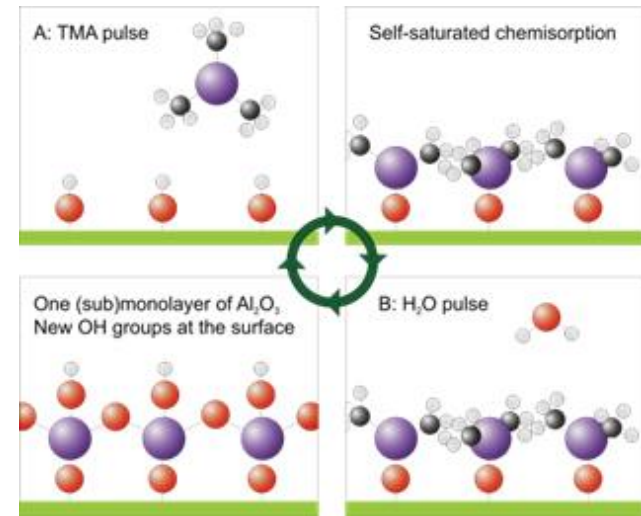


- ✓ Atomic thickness control
- ✓ Superior uniformity
- ✓ Easily scalable

Atomic layer deposition (ALD)

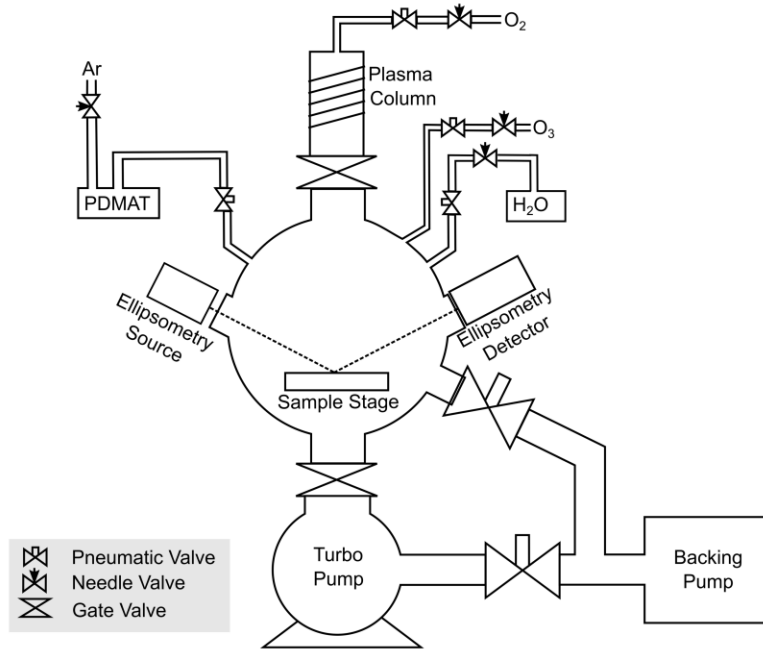


Self-limiting reactions between substrate and precursor gases!

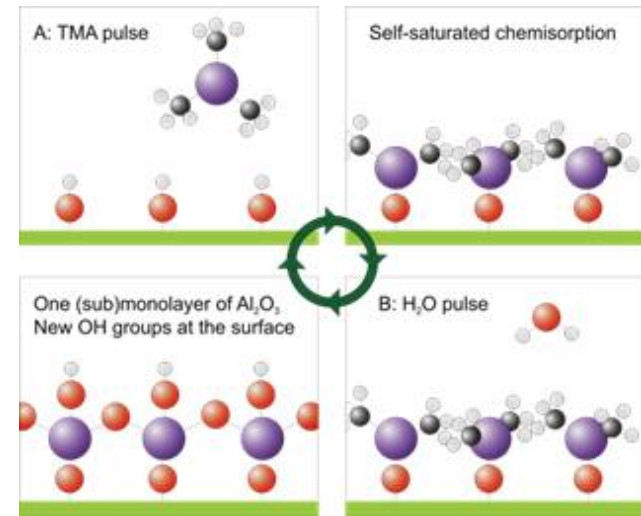


- ✓ Atomic thickness control
- ✓ Superior uniformity
- ✓ Easily scalable
- ✓ Wide variety of materials

Atomic layer deposition (ALD)



Self-limiting reactions between substrate and precursor gases!



- ✓ Atomic thickness control
- ✓ Superior uniformity
- ✓ Easily scalable
- ✓ Wide variety of materials
- ✗ Slow

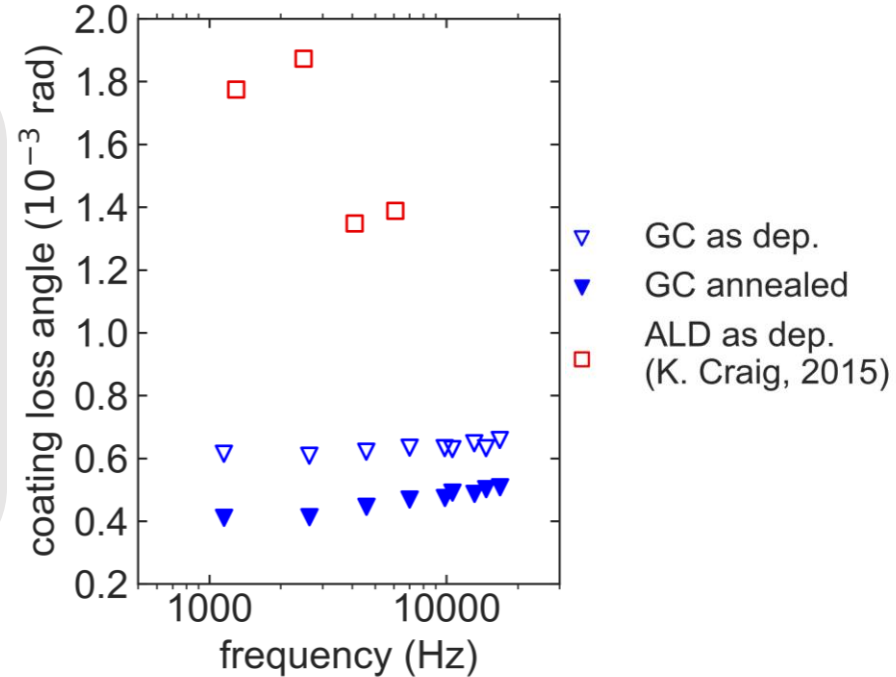
ALD Ta_2O_5



An earlier study found a very high loss of ALD tantala

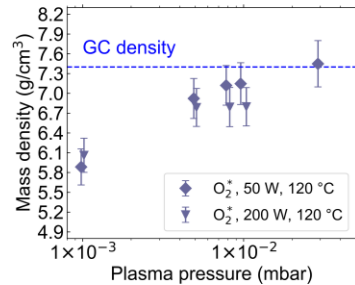
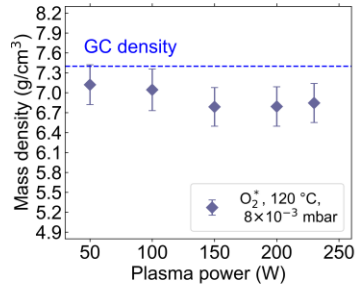
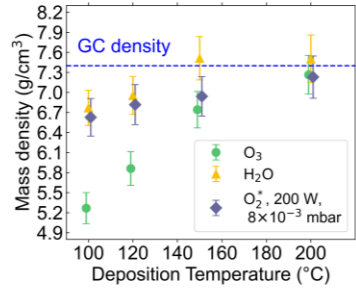


However, the process details were not given, and ALD has a lot of parameters that can be optimised

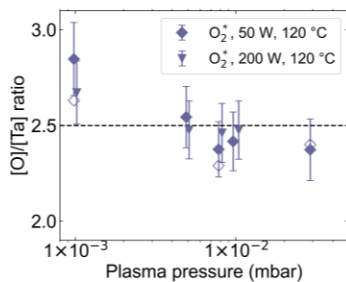
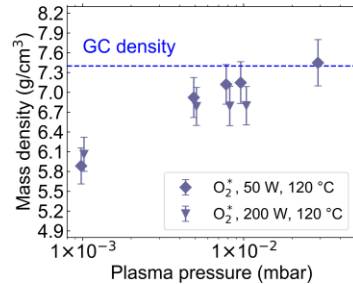
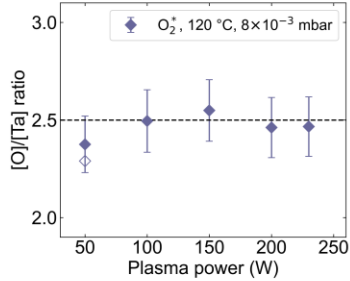
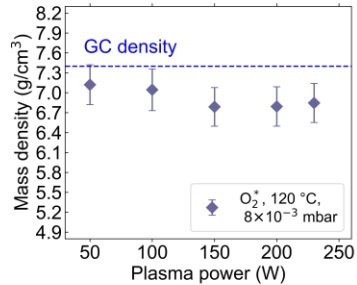
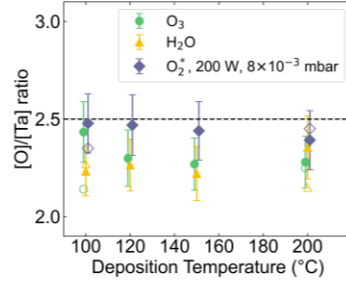
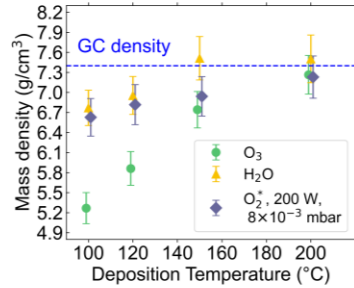


Process optimisation

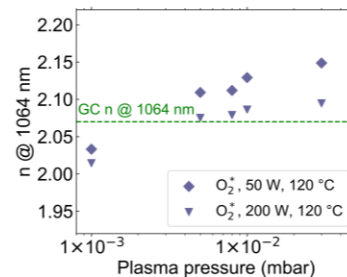
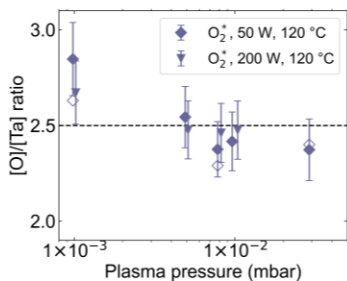
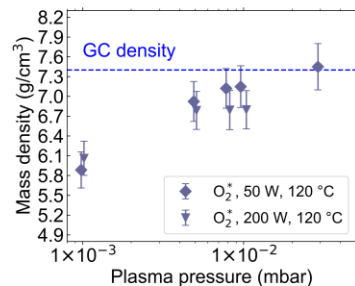
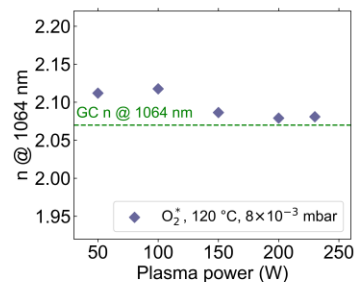
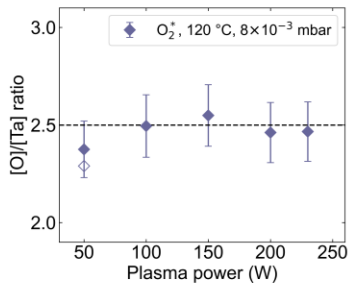
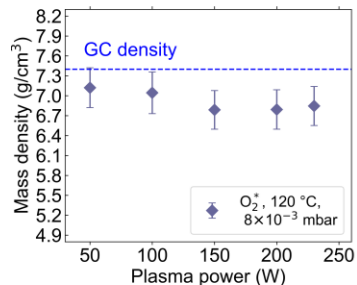
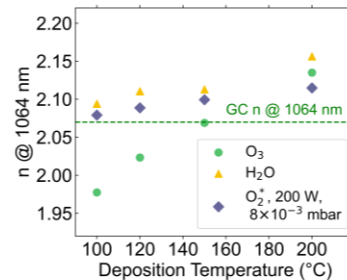
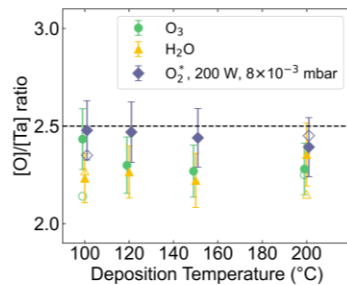
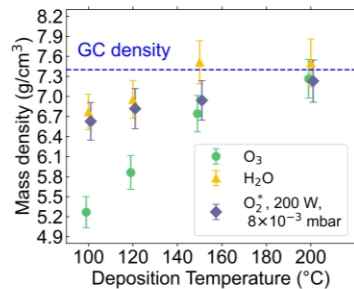
Process optimisation



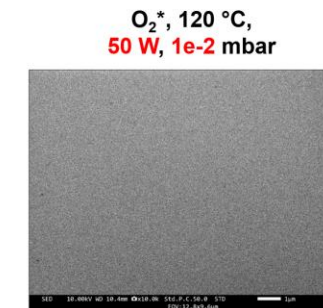
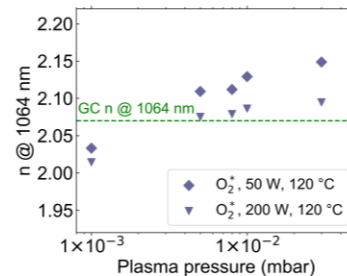
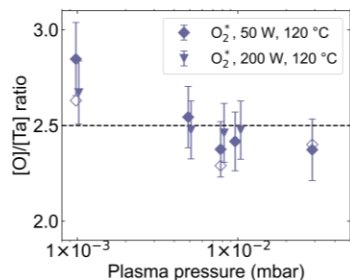
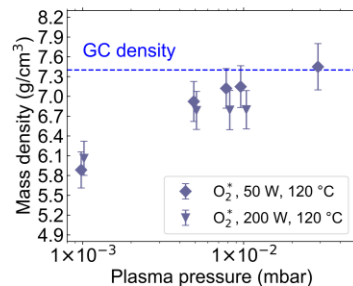
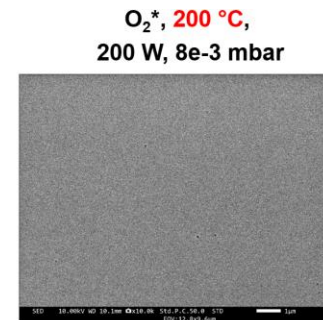
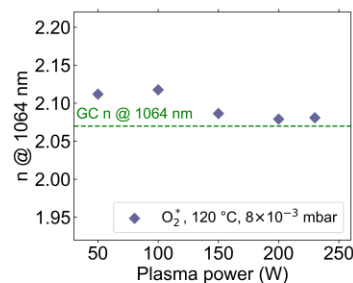
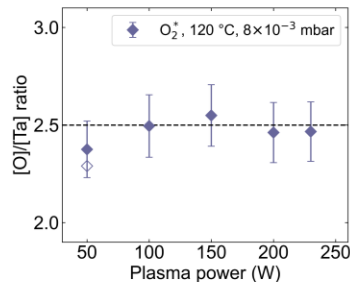
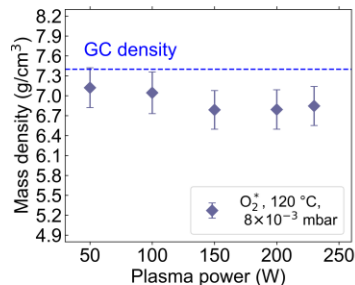
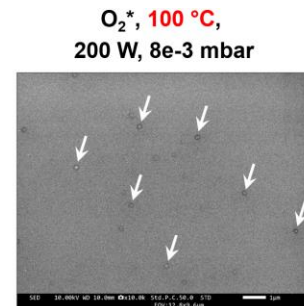
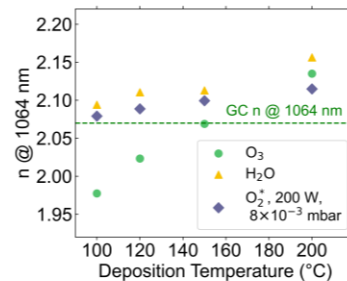
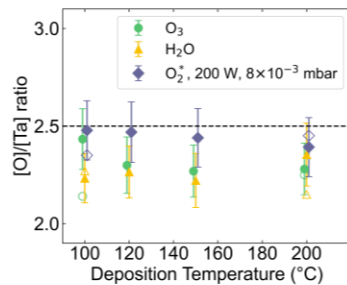
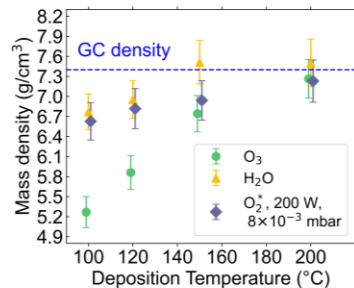
Process optimisation



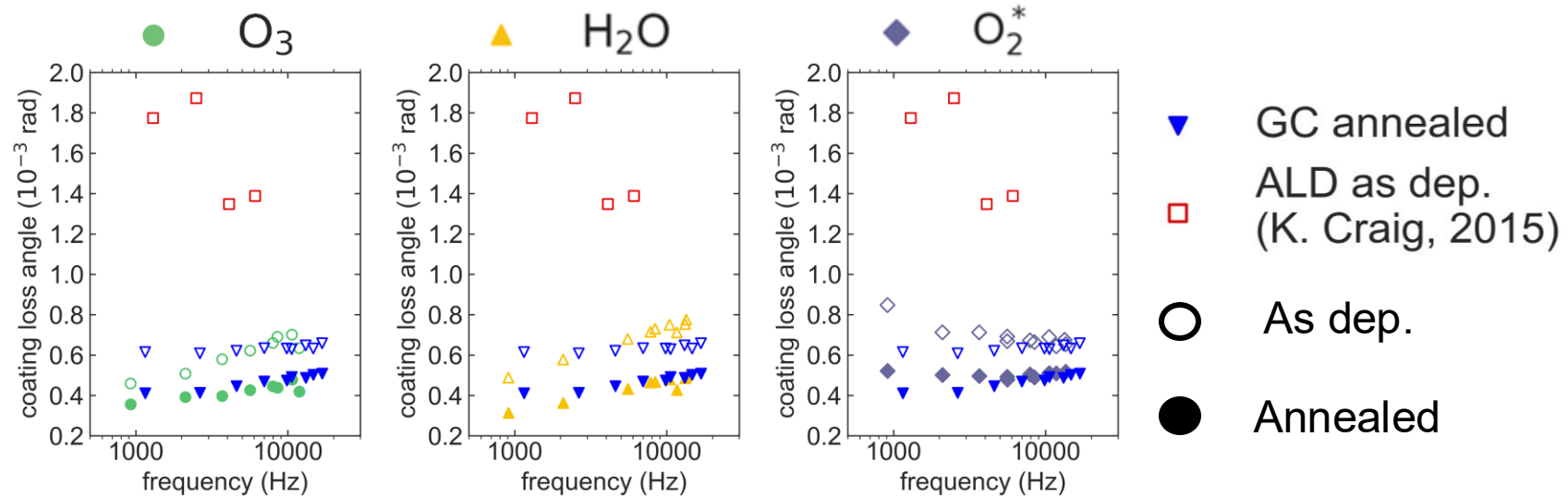
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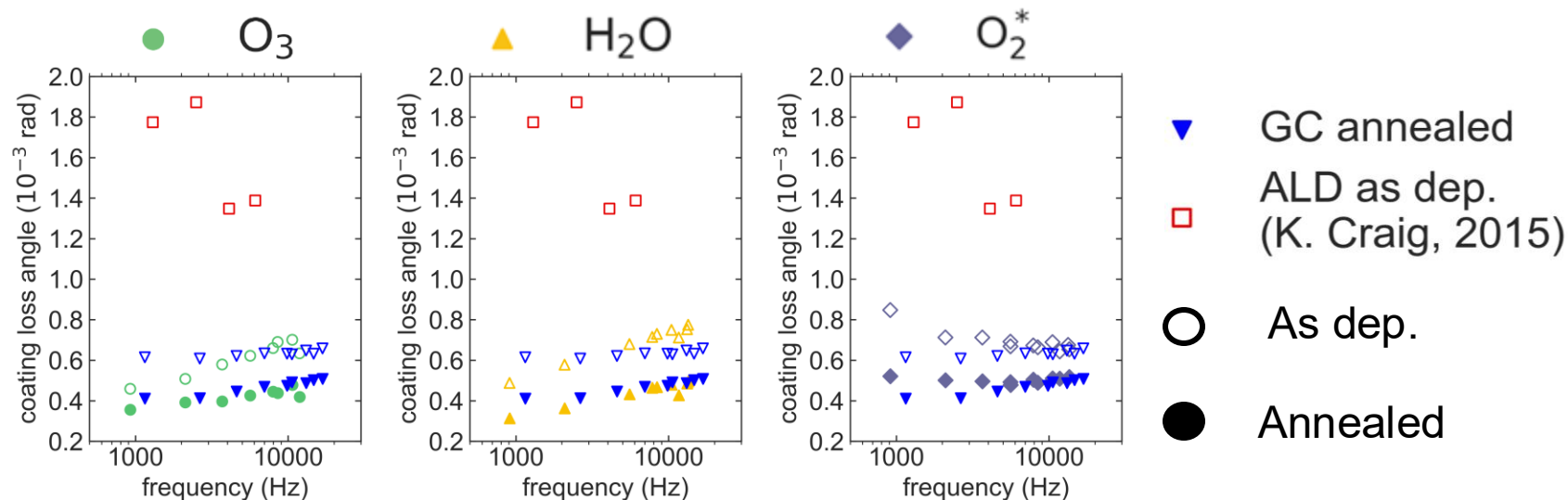
Process optimisation



Mechanical loss and optical absorption



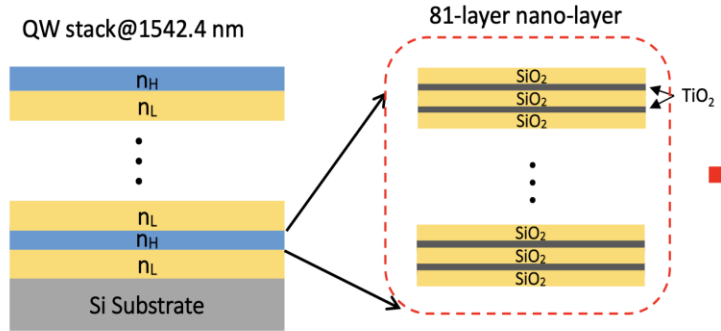
Mechanical loss and optical absorption



Co-reactant	State	Thickness (nm)	Abs. @ 1550 nm (ppm)	k @ 1550 nm	n @ 1550 nm	n @ 1064 nm
O ₃	as dep.	289	15.1	6.4×10^{-6}	2.02	2.04
	annealed	305	60.0	2.4×10^{-5}	2.04	2.05
H ₂ O	as dep.	381	68.7	2.2×10^{-5}	2.09	2.10
	annealed	375	52.7	1.7×10^{-5}	2.09	2.10
O ₂ [*]	as dep.	300	6.60	2.7×10^{-6}	2.08	2.09
	annealed	309	2.75	1.1×10^{-6}	2.08	2.09

Future perspective: atomically layered laminates

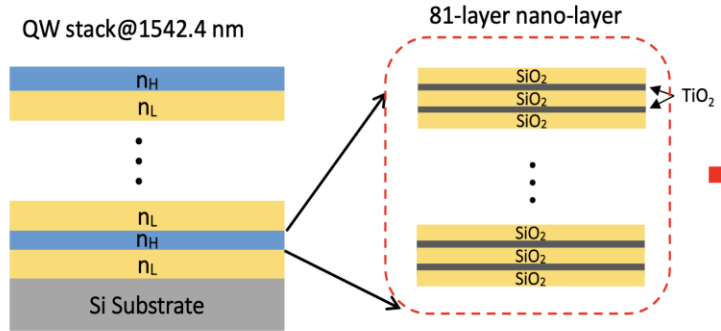
Engineering of refractive index and crystallisation temperature



	n	κ	d (nm)
TiO_2	2.27	1.1×10^{-5}	1.8
SiO_2	1.44	0	3.6

Future perspective: atomically layered laminates

Engineering of refractive index and crystallisation temperature

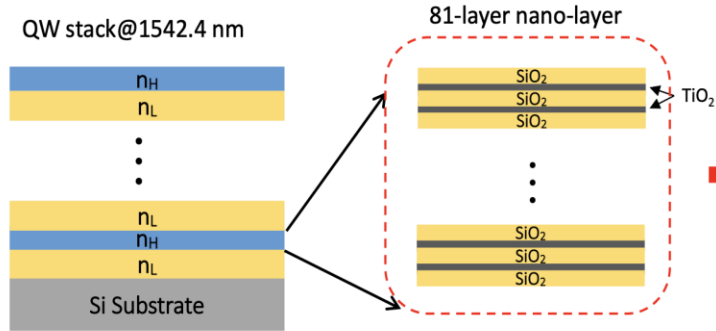


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**IBS limited
resolution**

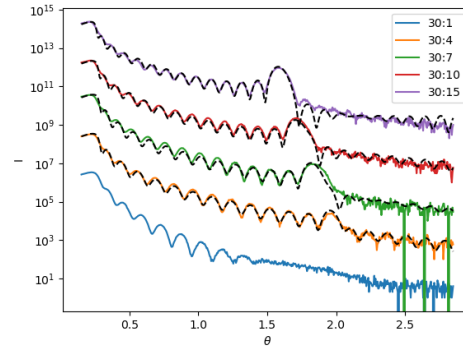
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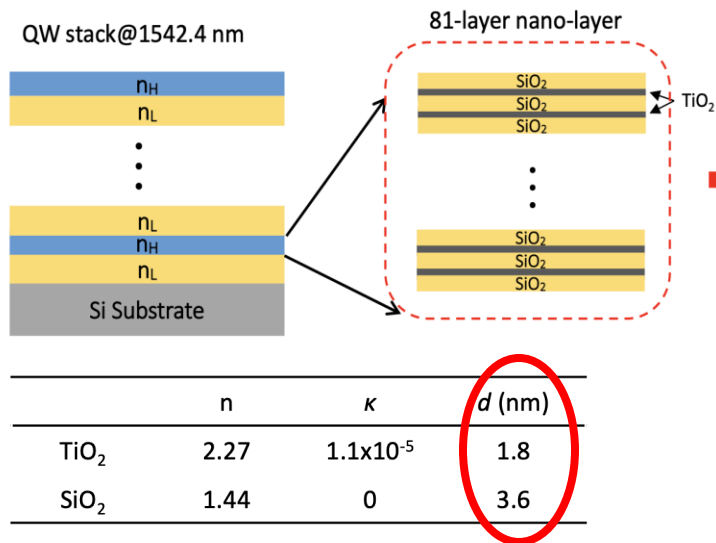
	TiO ₂ (nm/layer)	SiO ₂ (nm/layer)
14(30+1)	?	?
14(30+4)	1.9	0.2
14(30+7)	2.0	0.3
14(30+10)	2.1	0.4
14(30+15)	2.0	0.6

ALD: down to 0.1 nm

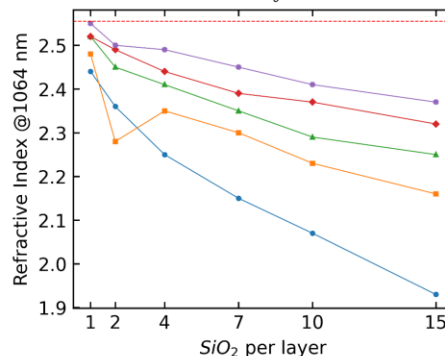
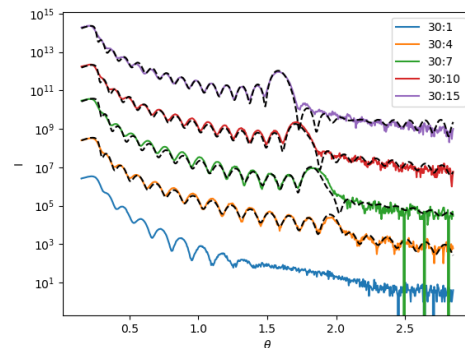
Very controllable and reproducible

Future perspective: atomically layered laminates

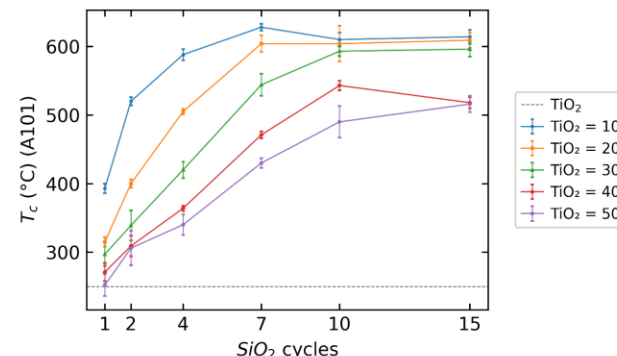
Engineering of refractive index and crystallisation temperature



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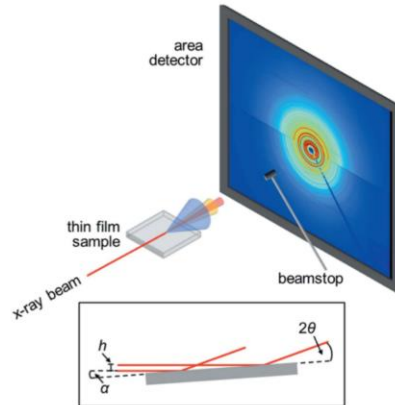
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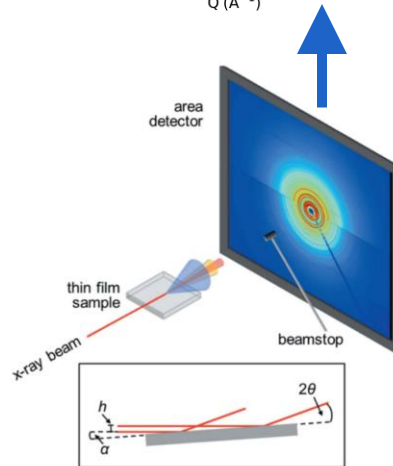
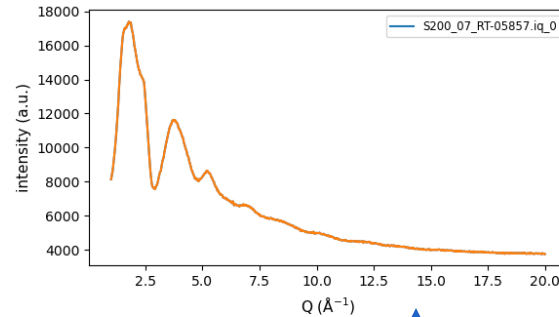
ALD: down to 0.1 nm
Very controllable and reproducible

X-ray characterisation of mirror coatings

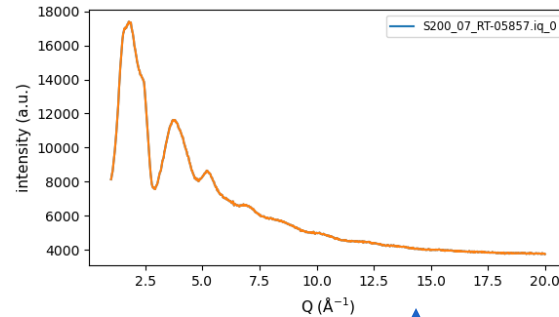
Structural characterisation of amorphous layers by total x-ray scattering experiments



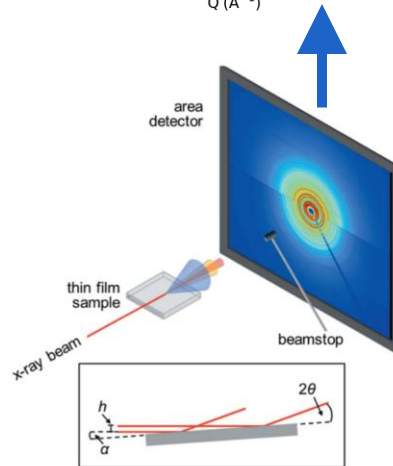
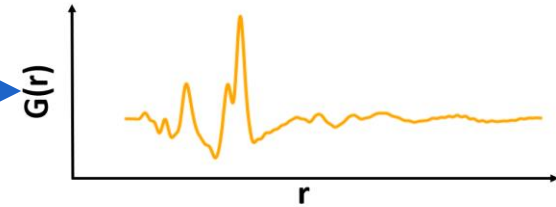
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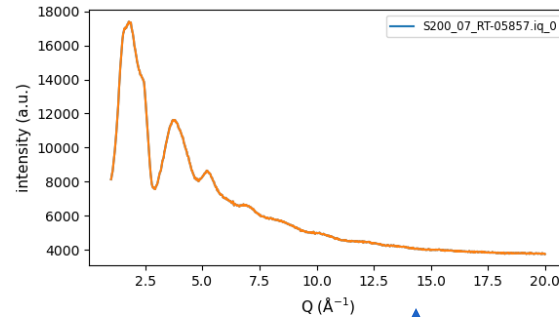
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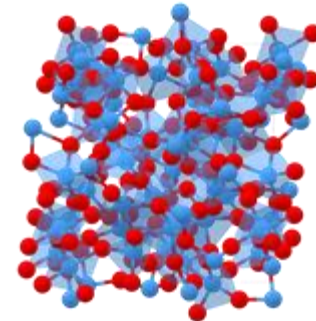
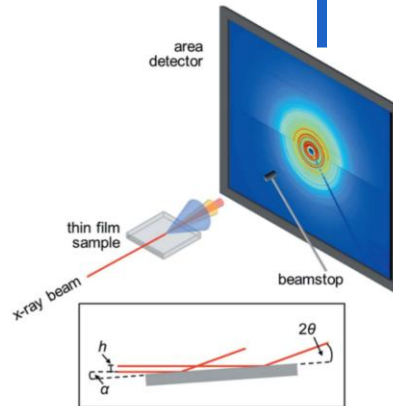
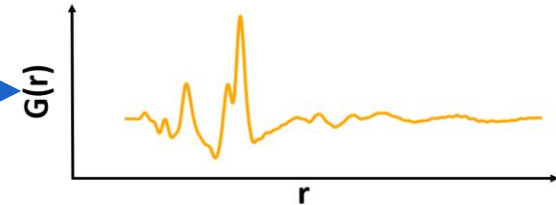
Pair distribution function (PDF)



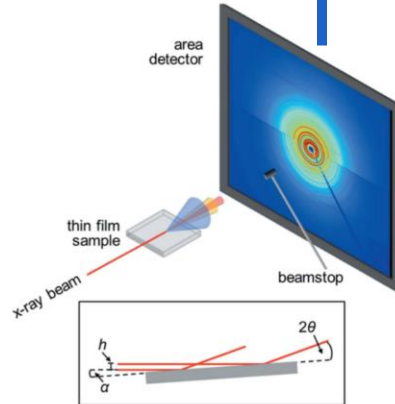
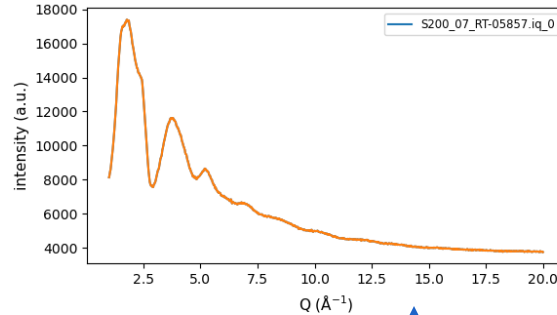
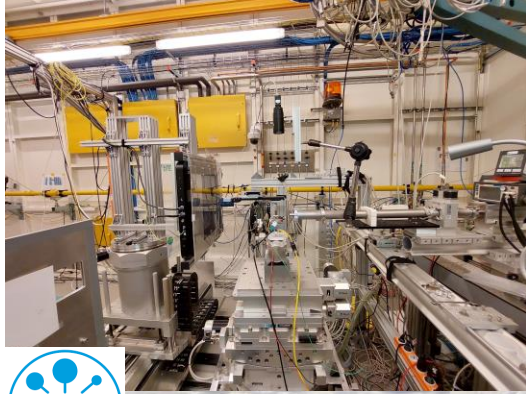
Structural characterisation of amorphous layers by total x-ray scattering experiments



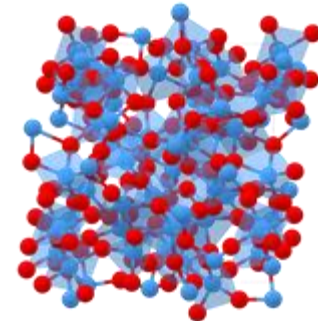
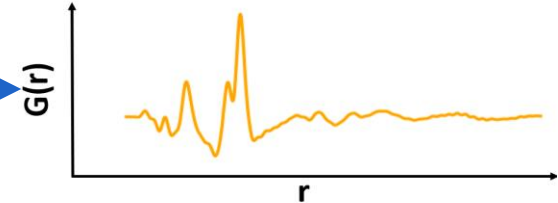
Pair distribution function (PDF)



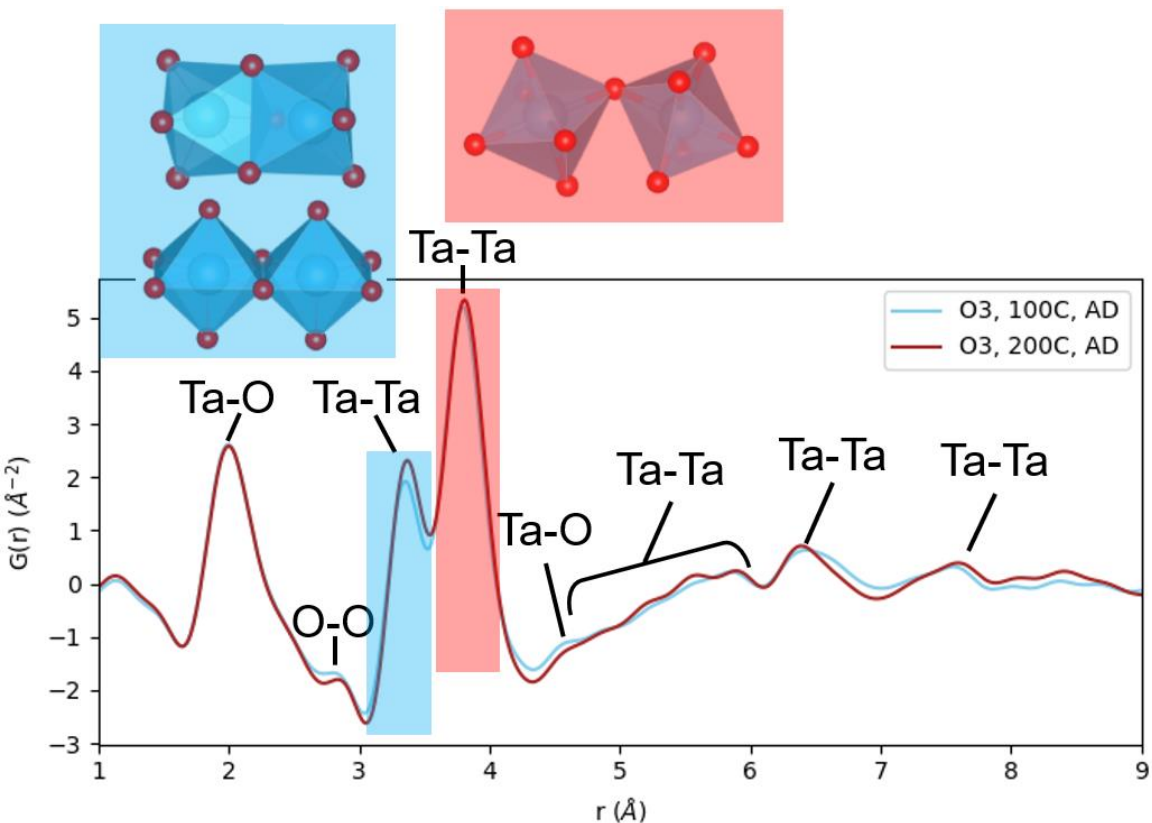
Structural characterisation of amorphous layers by total x-ray scattering experiments



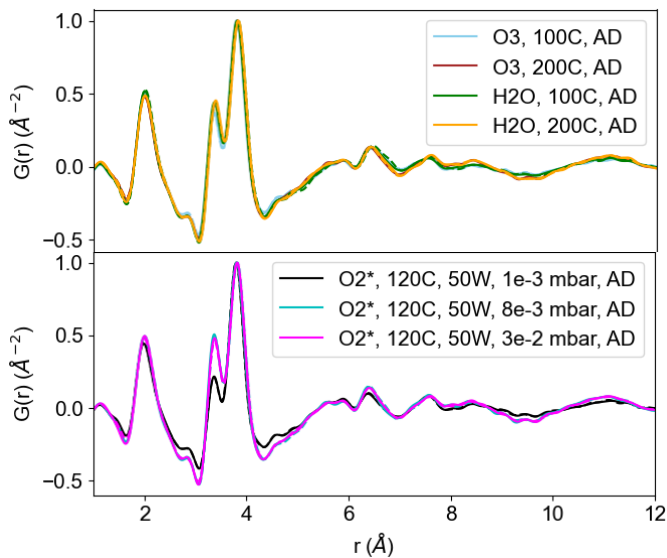
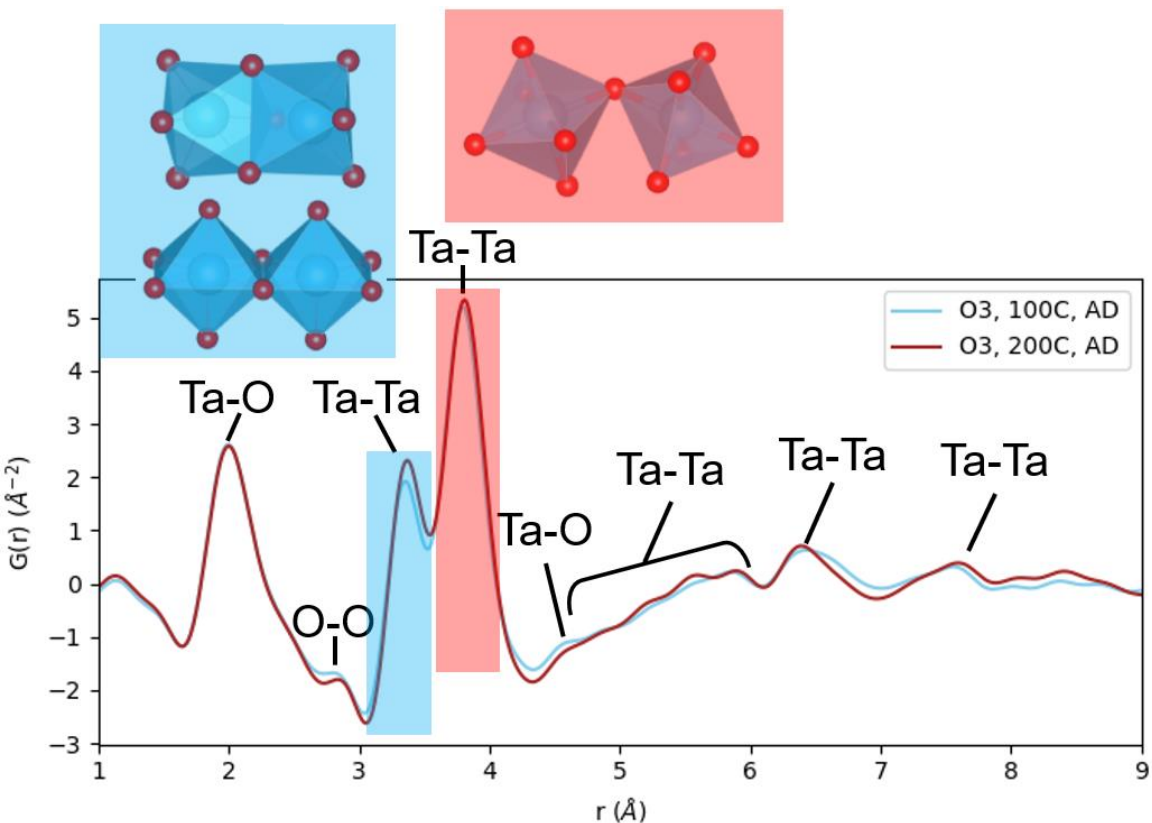
Pair distribution function (PDF)



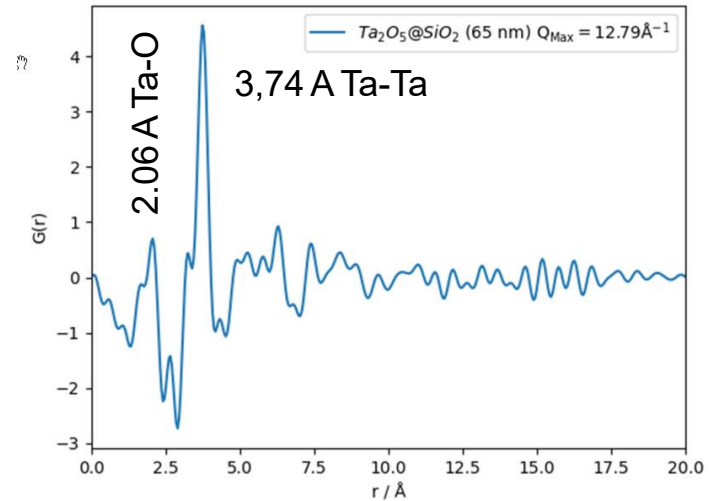
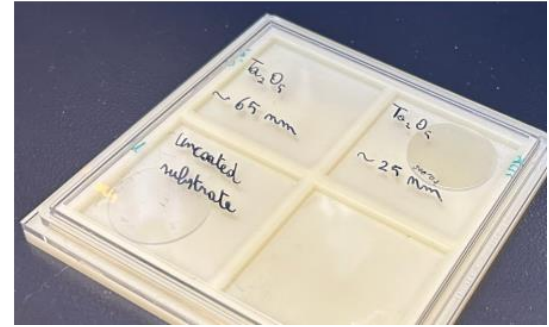
PDF of Ta_2O_5 coating measured by GI-PDF @ DESY



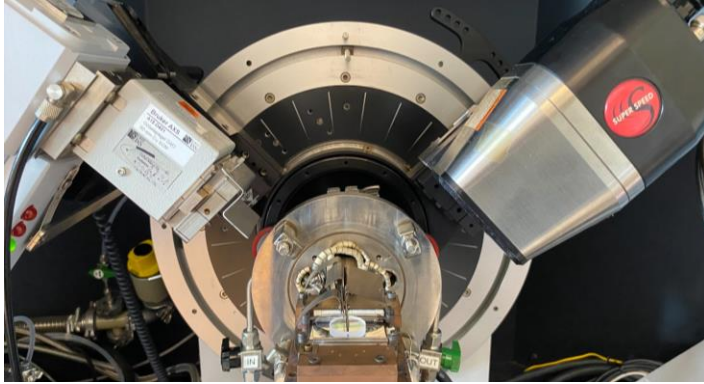
PDF of Ta_2O_5 coating measured by GI-PDF @ DESY



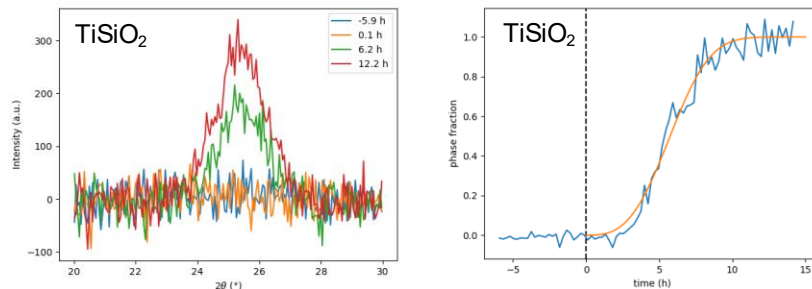
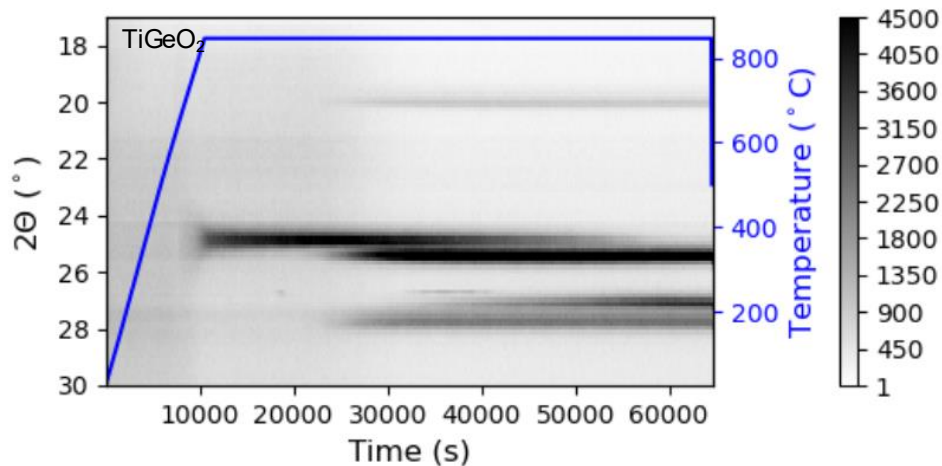
IRI proposal: lab tool total x-ray scattering @ UGent



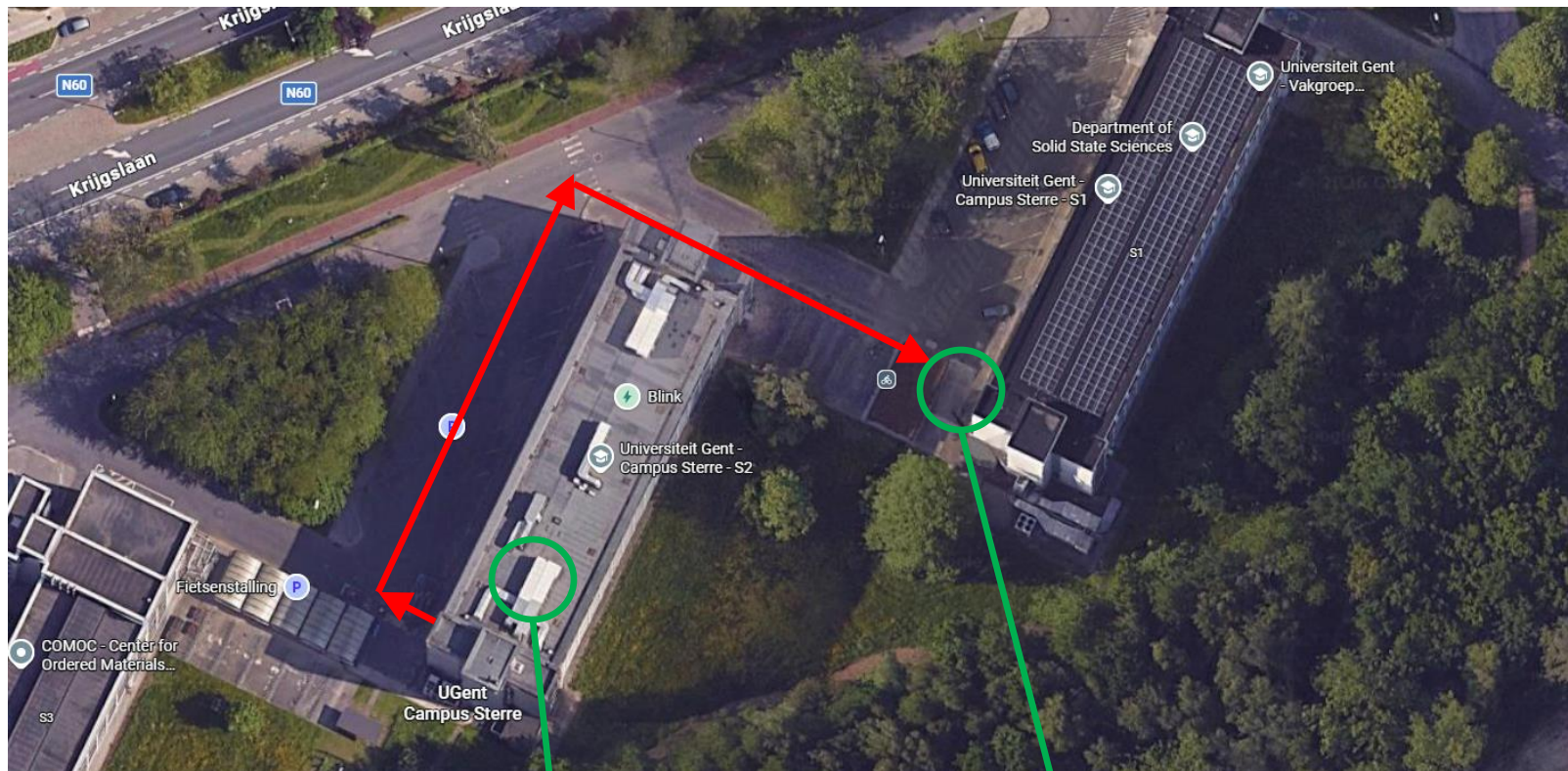
X-ray diffraction to optimise post-deposition anneal TiGeO_2 and TiSiO_2 coatings for VIRGO



X-ray diffraction to optimise post-deposition anneal TiGeO_2 and TiSiO_2 coatings for VIRGO



CoCooN lab tour during lunch break



You are here

Start of lab tour